Barrier RF Stacking Study

1. Goals:

- Near term To increase proton intensity (protons per second, or pps) on the p-bar target by 50%:
 - o Present: 4.5e12 protons every 1.467 seconds (22 Booster cycles).
 - o Stacking goal: 9e12 protons every 2 seconds (30 Booster cycles).
- Medium term To increase proton intensity (protons per second, or pps) on the NuMI target by 60%:
 - o MI baseline: 3e13 protons every 1.867 seconds (28 Booster cycles).
 - Stacking goal: 6e13 protons every 2.333 seconds (35 Booster cycles).

2. Status as of September 2002:

- Paper study is finished. Main results:
 - a. Can stack 2 Booster batches into the size of one Booster batch in the MI for p-bar production.
 - b. Can stack 12 Booster batches into the size of six Booster batches in the MI for NuMI.
 - c. Longitudinal emittance blow-up is about a factor of 3 (from 0.1 eV-s to 0.32 eV-s).
 - d. Key issue is that the Booster beam must have a small $\Delta p/p$ to start with (required ΔE about ± 6 MeV).
 - e. Compared with the slip stacking (another proposed scheme), one main advantage of the barrier rf stacking is smaller beam loading effects thanks to lower peak beam currents.
- Beam experiments and hardware are in preparation.

3. Experiments in the Recycler:

• Goal: To verify the simulation results.

- Recycler proton beam: 4 bunches (2.5 MHz) per injection from the MI. Longitudinal emittance = 2.5 eV-s per bunch. Assuming parabolic distribution, this gives ±4.7 MeV in energy spread.
- Recycler wideband rf: 2 kV maximum.
- Two experiments:
 - a. Beam squeezing at various barrier bucket moving speed.
 - b. Stacking using off-momentum injected beams.
- Key parameter $\Delta p/p$ measurement:
 - a. Schottky spectrum:
 - > Doable for unbunched beams.
 - ➤ Difficult for bunched beams.
 - ➤ Our case is somewhat in between: The beam is debunched (no synchrotron oscillation), whereas there is a strong coherent gap signal.
 - b. Bucket scanning.

4. Experiments in the Booster:

- Goal: To obtain small $\Delta p/p$ beam at Booster extraction.
- Experiments:
 - a. To suppress coupled bunch instabilities:
 - Feedback Longitudinal damper. (D. Wildman)
 - ➤ Landau damping To operate one rf cavity at h=83.
 - b. To lower $\Delta p/p$ of the beam at extraction:
 - > Bunch rotation.
 - ➤ Adiabatic compression.

5. Hardware Development:

- 1) Barrier rf system for the MI:
 - Goal: To build an 8-10 kV barrier rf system using Finemet cavities and high voltage fast switches.
 - Cavity: Based on the design of an rf chopper that was built by a Fermilab-KEK collaboration through a US-Japan Accord. Hitachi Metals will supply the Finemet cores.

• Switch circuit: Also based on the design of the rf chopper. Behlke will supply the switches (solid state HTS series). However, there is an important difference between the chopper circuit and the barrier rf circuit. The former uses a pair of +V and -V pulses. The latter requires a zero-voltage gap between +V and -V pulses. Therefore, the circuit needs to be modified.

2) MI rf modification: (J. Griffin)

- Goal: To reduce the beam loading effect by a factor of 3-4.
- Method: To lower the screen voltage from +2 kV to -100 V.

Barrier RF Stacking for NuMI 6-Batch Operation (B. Ng)

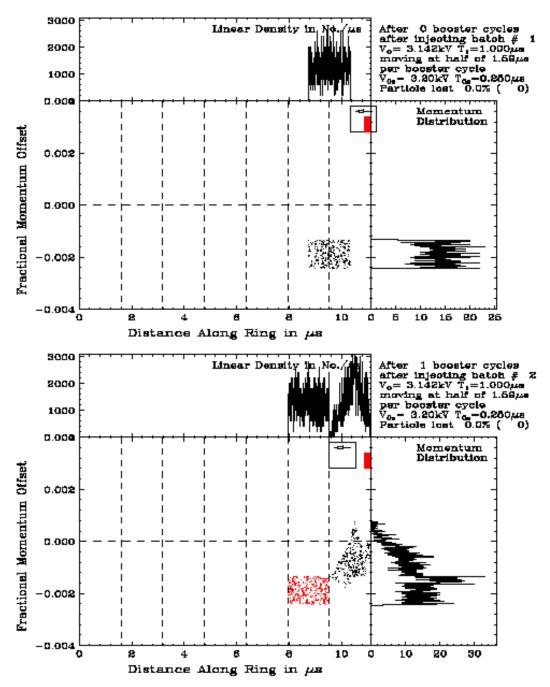


Figure 6: (color) Top: First batch (black) is injected between $5.5T_b$ and $6.5T_b$ with the right side touching the left side of the moving barrier, illustrated as an unfilled box with an arrow. Bottom: After one booster cycle, all particles in the first batch have just cleared the left side of the moving barrier, which is at $6.0T_b$. The second batch (red) is now injected between $5.0T_b$ and $6.0T_b$. Moving barrier has width $T_1 = 1.0 \,\mu s$ and strength $V = 3.1421 \,\mathrm{kV}$. Vertical dashed lines are spaced at T_b .

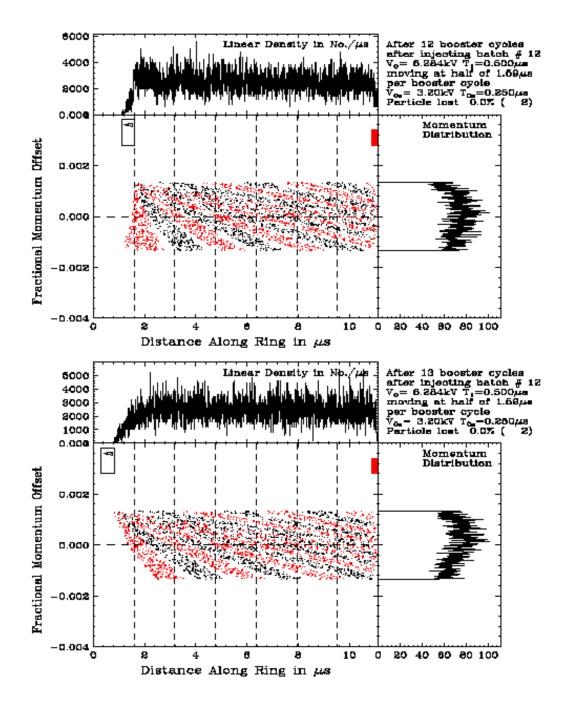
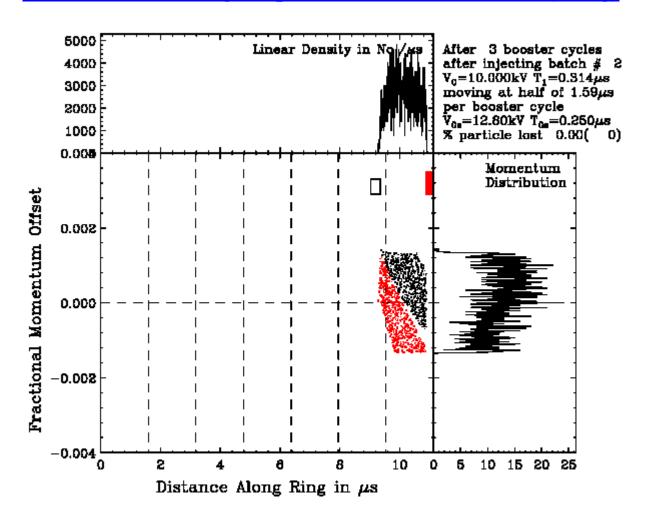


Figure 8: (color) Same as Fig. 7, but with the width of the moving barrier reduced to $0.5 \mu s$ and strength increased to 6.2842 kV. At injection of first batch, left side of barrier was placed at $6.7T_b$. Top: One booster cycle after the injection of the 12th batch between $0.2T_b$ and $1.2T_b$, or 12 booster cycles after the injection of the first batch. Bottom: Another booster cycle later.

Barrier RF Stacking for p-bar 2-Batch Production (B. Ng)



Barrier RF Experiments in the Recycler (C. Bhat)

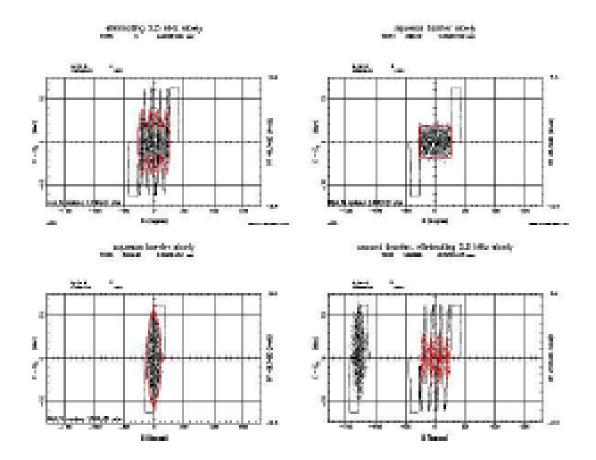


FIGURE 3. Longitudinal beam dynamics simulation results for beam stacking. Shown are distribution of beam particles in $(\Delta E, \Delta \phi)$ -space. The rf wave forms and buckets are also shown. For details see the text.

Properties of Finemet (a nanocrystal magnetic alloy)

(a) Finemet vs. Ferrite (C. Ohmori et al.)

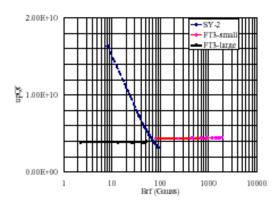


Figure 2: Magnetic flux density dependence of magnetic materials. SY2 is a typical ferrite core and the magnetic flux density dependence was observed. FT3-small and large are MA cores of 570mm O. D. and 70 mm O.D., respectively. The MA cores have a constant shunt impedance up to 2 kGauss.

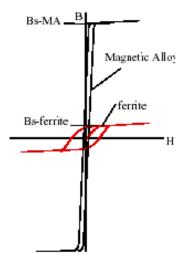


Figure 1: The hysteresis curves of magnetic materials. $B_{\rm B}$ means the saturation magnetic flux density. The usable $B_{\rm RF}$ is much smaller than $B_{\rm B}$.

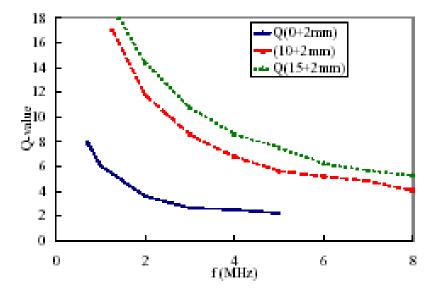


Figure 10: The O-value of the cut core vs. gap height.

(b) Finemet (nanocrystal) vs. Metglas (amorphous) and Silicon Steel (macrocrystal) (A.W. Molvik and A. Faltens)

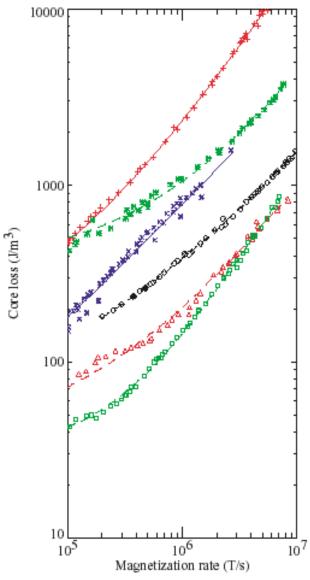
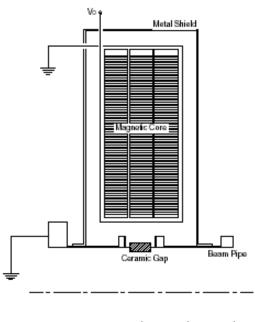


FIG. 6. (Color) Core loss versus magnetization rate for six cores, all annealed after winding. From the top, these are (+, red, solid line) 50 μ m thick 3% silicon steel with $\Delta B = 3.3$ T; (*, green, dashed line) 25 μ m thick 3% silicon steel with $\Delta B = 3.0$ T; (×, blue, solid line) METGLAS 2605 SA1 with magnesium methylate insulation with $\Delta B = 2.7$ T; (\diamondsuit , black, dashed line) METGLAS 2605 SC cowound with mica paper insulation with $\Delta B = 2.4$ T; (\triangle , red, dashed line) FINEMET FT-2H with $\Delta B = 2.4$ T; and (\square , green, dashed line) FINEMET FT-1H with $\Delta B = 2.1$ T. Both FINEMET alloys are insulated with a glass coating.

RF Chopper Cavity made of Finemet (Fermilab/KEK)



0 5 10(cm)

Figure 2: A test cavity used in the measurements. It consists of a magnetic core, a metal shield, a one-turn coil and a stainless steel beam pipe with a ceramic gap.

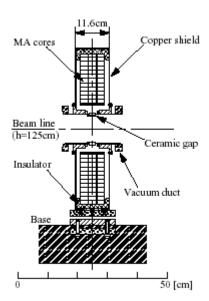


Figure 2: Side view of the chopper. Three magnetic-alloy cores with 504mm ϕ_{out} x 158mm ϕ_{in} x 25mm thickness are used. An one-turn coil is wound around the cores.

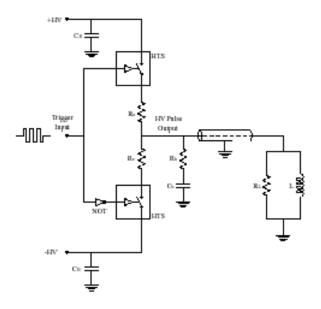


Figure 5: A circuit diagram of a bipolar (push-pull) high voltage source using two HTS transistors as the switches.



Figure 1: Chopper cavity installed at the HIMAC facility. A constant-energy beam from an ion source comes from the right-hand side, and its energy is modulated by +-5% at the chopper cavity. The downstream RFQ is located at the left-hand side, which is at the other side of the wall.

Comparison: Ferrite (4M2) vs. Finemet

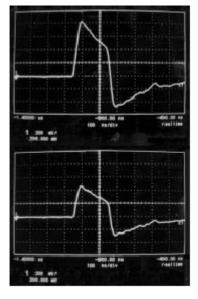


Figure 4: The primary and secondary voltage waveform when a 4M2 core is used.

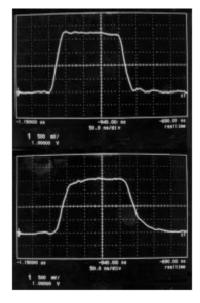
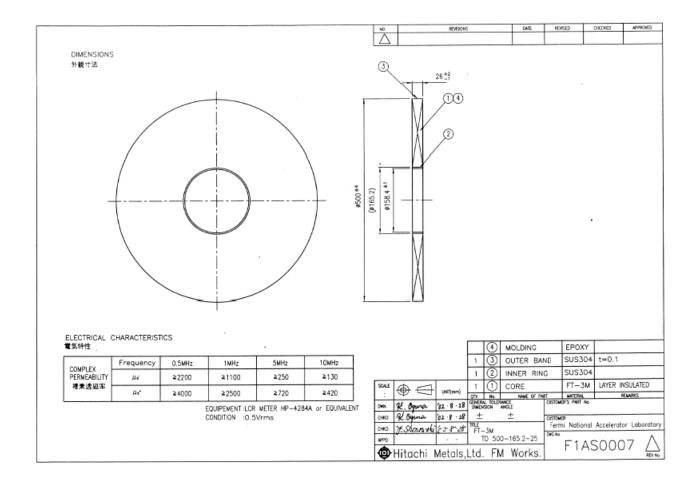


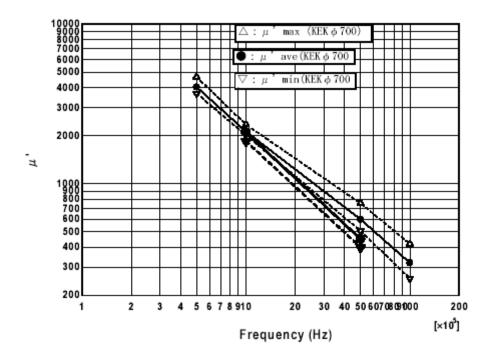
Figure 3: The primary and secondary voltage waveform when a Finemet core is used. The rise-time is about 40 ns.

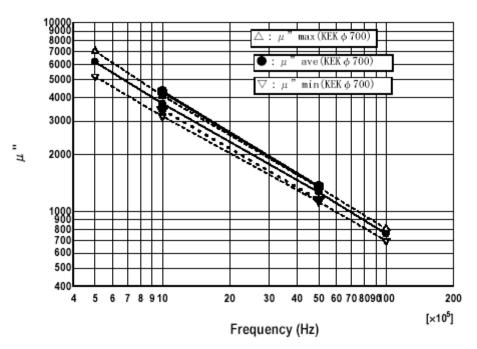


Finemet Core Design



Sample Finemet Core Measurement Data

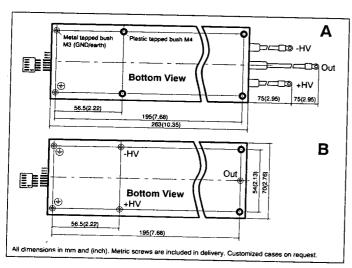




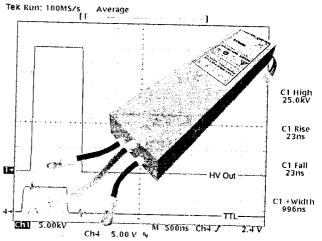
FAST HIGH VOLTAGE TRANSISTOR SWITCHES

The switching modules of the series HTS-GSM consist of two identical MOSFET switching paths, that form a so-called half bridge circuit respectively push-pull circuit. Both switching paths are controlled by a common driver, which also provides a logic signal negation for one of the switches. The switches are mutually passively locked, so that a short in the bridge is excluded under all circumstances, even then, if the control input is disturbed by electromagnetic interferences (due to bad EMC design, for example). Especially in pulse generator applications with capacitive load, the push-pull principle has considerable advantages in comparision with the conventional circuitry using a single-switch with working resistor. Push-pull circuits do not require large energy storage capacitors for a low pulse droop and, because there are no working resistor power losses, the efficiency of a push-pull pulser is excellent regardless to pulse width, frequency and duty cycle. The pulsers draw only currents for charging the connected load capacitance. Thanks to an extremely precise timing of the switches, there are also almost no cross currents in the bridge, except peak charging currents of the switch natural capacitances.

The switches are controlled by positive going signals of 3 to 10 Volts amplitude. Fault conditions as overfrequency, thermal overload (long-term overload) and incorrect auxilliary supply set the switching path A in off-state and the switching path B in onstate. Faults are indicated as a "L" signal at the fault signal output. Without 5VDC supply both switching paths (A and B) are in off-state. That means, without 5VDC the output potential could be undefined, if the HV is still applied. To ensure a defined high voltage output potential in such cases, pull-up or pull-down resistors must be connected to the output. For further design recommendations please refer to the general instructions.



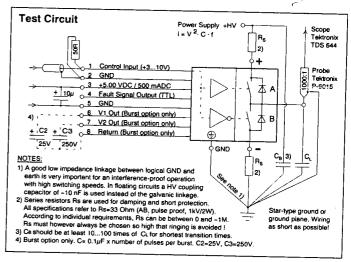
HTS 161-06-GSM 2x16kV / 60A HTS 301-03-GSM 2x30kV / 30A

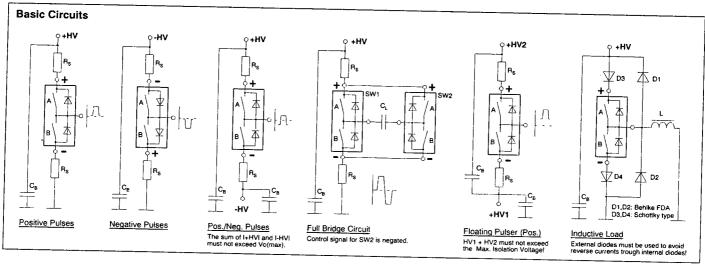


- Fast transition times, rise time and fall time ~20 ns
- Variable pulse width from 200 ns to infinity
- No pulse droop and very low ripple on the pulse top
- No working resistor power, small buffer capacitors

PUSH-PULL

- Patented -Made in Germany MOSFET TECHNOLOGY





TECHNICAL DATA

Specification	Symbol	Condition / Comment			161-06-GSM	301-03-GSM	Unit	
Maximum Operating Voltage	V _{O(max)}	l _{off} < 10 μADC			2 x 16	2 x 30	kVDC	
Minimum Operating Voltage	V _{O(min)}	Increased transition times below 0.1 x V _{O(max)}				0		kVDC
Typical Breakdown Voltage	V _{br}	Static voltage, I _{off} > 1 mADC, , T _{case} = 70 °C				2 x 18	2 x 36	kVDC
Galvanic Isolation Voltage	Vi	Standard plastic case (see note 1) Option 08A (Pigtail version only, see drawing A) Option 08B (Pigtail version only, see drawing A)		25	40			
,				40	•			
				80	80	kVDC		
Maximum Peak Current	I _{P(max)}	$T_{case} = 25^{\circ}C$ $t_p < 10 \mu s$, duty cycle < 1%		2 x 60	2 x 30 ·	ADC		
Max. Continuous Load Current	ار	T _{case} = 25°C	Standard plastic case (see note 1)		2 × 0.7	2 x 0.33		
		T _{fin ₂} 25°C	Opt.03, i	ncreased t	hermal conductivity	2 x 0.86	2 x 0.41	
	:		Opt. 04,	cooling fir	ns (air >4m/s)	2 x 2.2	2 x 1.05	ADC
Static On-Resistance	R _{stat}	T _{case} = 25°C	0.1 x l _{P(c}	naxi		2 x 18	2 x 72	
			1.0 x l _{P(r}	nax)		2 x 40	2 x 180	Ω
Maximum Off-State Current	l _{off}	0.8xV _{o.} T _{case} = 2570°C, reduced l _{off} on request		10		μADC		
Propagation Delay Time	t _d	Resistive Load				190		ns
Typical Output Transition Time	t _{r.} t _f	0.8 x V _o R _s = 33		$R_s = 33 \Omega$, C _L = 10pF	10	20	
(Rise Time & Fall Time)	'' '	10-90%	I	-	, C _L = 50pF	15	35	
			1	_	, C _L = 100pF	17	50	
				$R_s = 33 \Omega$, C _L = 200pF	25	90	
				$R_s = 22 \Omega$, C _L = 1000pF	60	230	ns
Minimum Output Pulse Width	t _{p(min)}	Reduced output pulse width on request.		.20	0	ns		
Maximum Output Pulse Width	t _{p(max)}					No limitation, up to ∞		
Minimum Pulse Spacing	t _{ps(min)}	(Switch recovery time)				400		ns
Typical Output Pulse Jitter	ti	V _{aux} =5.0 VDC Fixed switching frequency, >2kHz			0.1			
	,	V _{tr} =5.0 VDC		_	ncy, <2kHz	5		ns
Max. Continuous Switching	f _(max)	Please note possible P _{d(max)} limitations.						
Frequency	,,	Increased switching frequency on request.				. 2		kHz
Maximum Burst Frequency	f _{b(max)}	Use option 01 for >10 pulses per 20µs burst				2.5		MHz
Maximum Continuous Power	P _{d(max)}	T _{case} = 25°C Standard plastic case (see note 1)		2 x 20				
Dissipation		T _{fin} = 25°C Opt. 03, incr. thermal conductivity		2 x 30				
	i	Opt. 04, air speed >4m/s (s. note 2)		2 x 200		Watts		
Linear Derating		Above 25 °C Standard plastic case Opt.03, incr. thermal conductivity Opt. 04, air speed >4m/s		2 x 0.44				
				mal conductivity	2 x 0.66			
				2 x 4.44		W/K		
Operating Temperature Range	To				-4070		°C	
Typical Natural Capacitance	C _N	Capacitance between the 0.1 x V _{O(max)}			< 9	00		
		terminals of one switch path 0.8 x V _{O(max)}			< 30		pF	
Typical Coupling Capacitance	Cc	Both switches against ground respectively control			< 30		pF	
Reverse Recovery Time	t _{rrc}	Important Note: Due to the high t _{rrc} of the parasitic diodes any						
of the intrinsic diodes (parasitic MOSFET diodes)		current reversal must be avoided! Unclamped inductive load or high stray inductance of wiring may cause a short circuit in the bridge. Danger of irreparable damage! Use serial resistors, snubbers or fast free-wheeling diode networks to avoid any current reversal.						
(parasitic MOSFET Glodes)					5001000		ns	
Auxiliary Supply Voltage	V _{aux}	Stabilized to ± 5%				5.00		VDC
Auxiliary Supply Current	laux	@f _{max} , (Limitation of approx. 1 A recommended)				600		mADC
Control Signal	V _{tr}	>3VDC recommended for low jitter				310		VDC
Fault Signal Output		Short circuit proof, source/sink Ready = High			≥4.0			
		current max.			Fault = Low	≤0.		VDC
Dimensions	LxWxH	Standard case (Without pigtails & opt. cooling fins)			263×70×35		mm³	
Weight		Standard plastic case			80			
	-	With option 04 (cooling fins in standard size)			1450		g	

Notes:

Ordering Information HTS 161-06-GSM Push-pull transistor switch HTS 301-03-GSM Push-pull transistor switch Option 01 High frequency burst Option 03 Increased thermal conductivity

Option 05 Option 06 Option 08A Option 08B High power metal case (on request) Printed circuit board version of HTS 301-03-GSM. 40kV isolation for HTS 161-06-GSM (pigtail version "A" only)

80kV isolation (pigtail version "A" only)

Non-isolated cooling fins (oil immersion for Vo >20 kV) Option 04

The standard case is _A" for the HTS 301-03-GSM and _B" for the HTS 161-06-GSM. Please refer to the drawing overleaf. Version _B" is optionally also available for the HTS 301-03-GSM (option 06) but only in connection with additional isolation measures (e.g. oil immersion) or in case of operating voltages less than _20 kVDC. The version "B" for attachment on printed circuit boards is preferred in high speed circuits with transition times in the order of 10 to 20 ns or in case of critical EMC aspects.

Cooling fins are not recommended if the HTS 301-03-GSM shall be operated in air above 20 kVDC. No limitations if operated in oil. Please consult factory for further oil cooling information.

Appendix. RF Cavity made of Finemet in the Main Injector (D. Wildman)



FIGURE 7. A 7.5 MHz Finemet rf cavity installed in the Fermilab Main Injector.